

FIG. 1 PRIOR ART

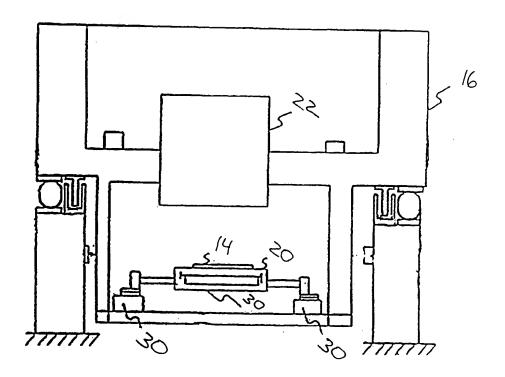


FIG. 2 PRIOR ART

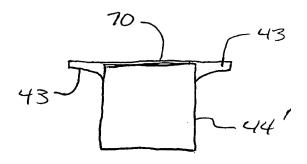
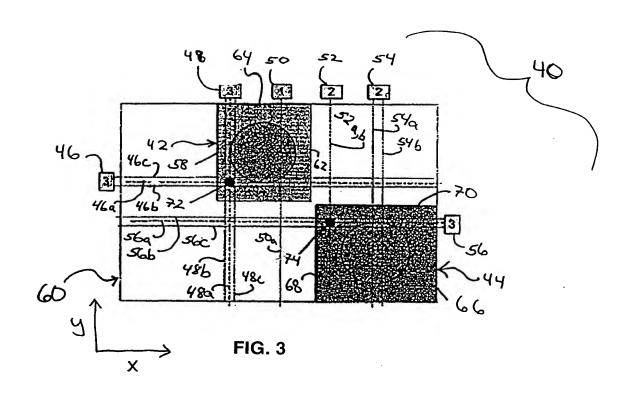
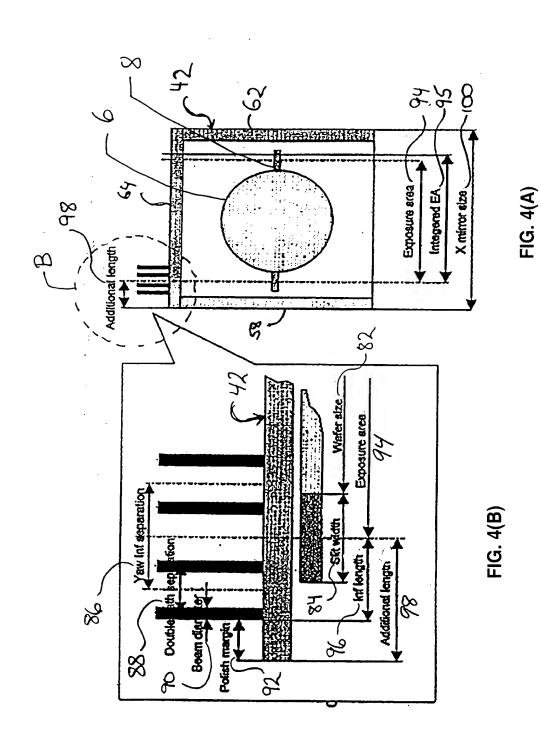


FIG. 3(A)





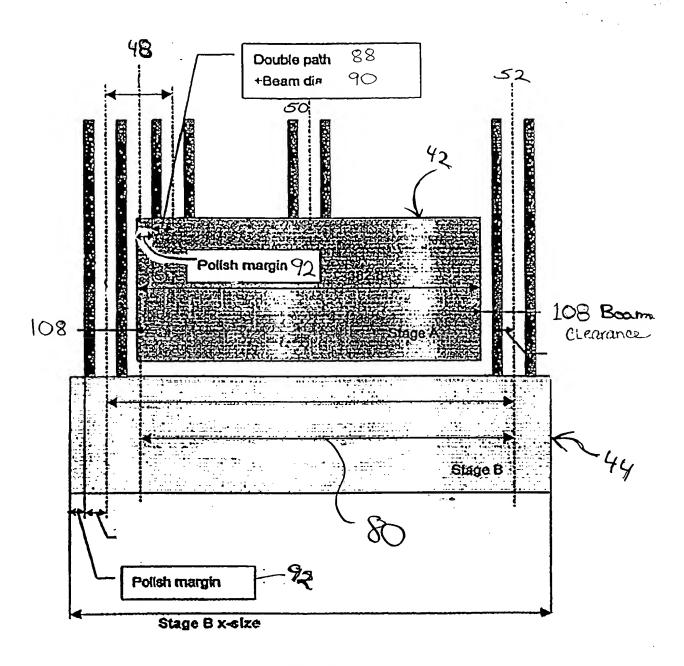


FIG. 5

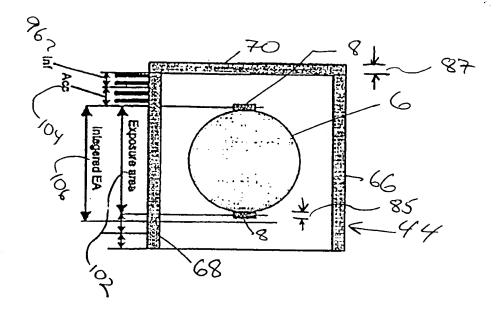


FIG. 6

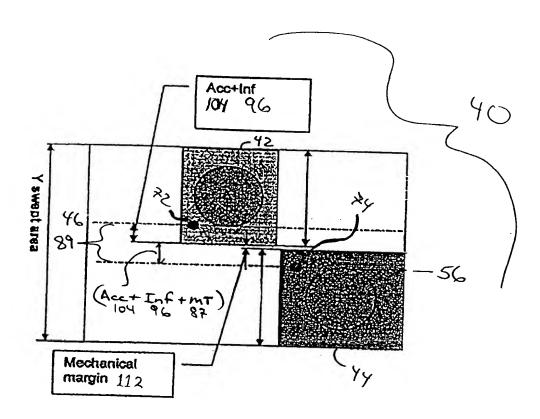
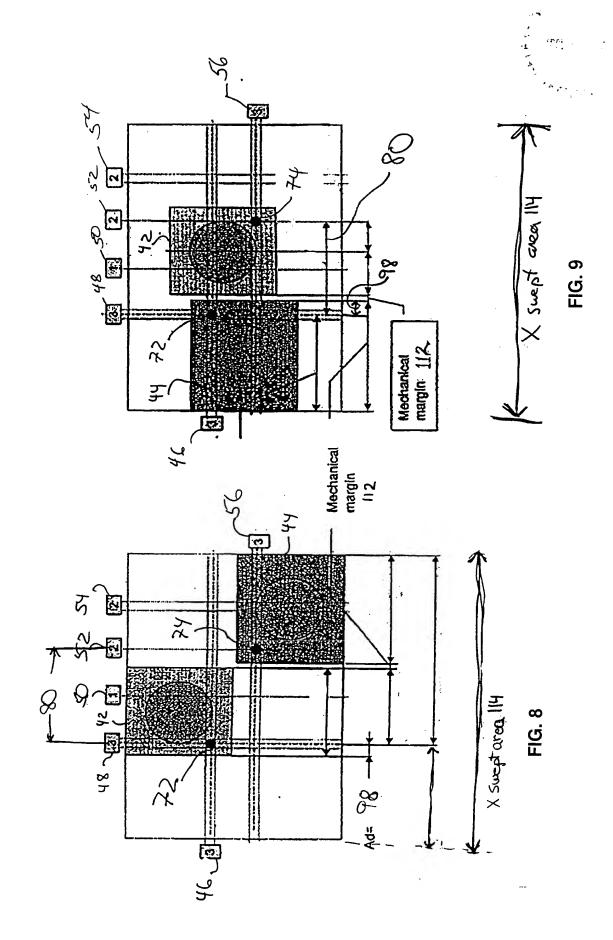
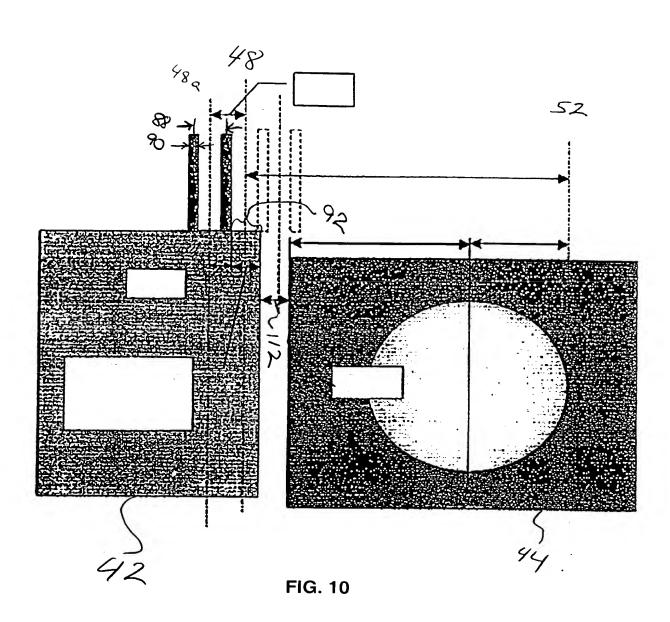


FIG. 7





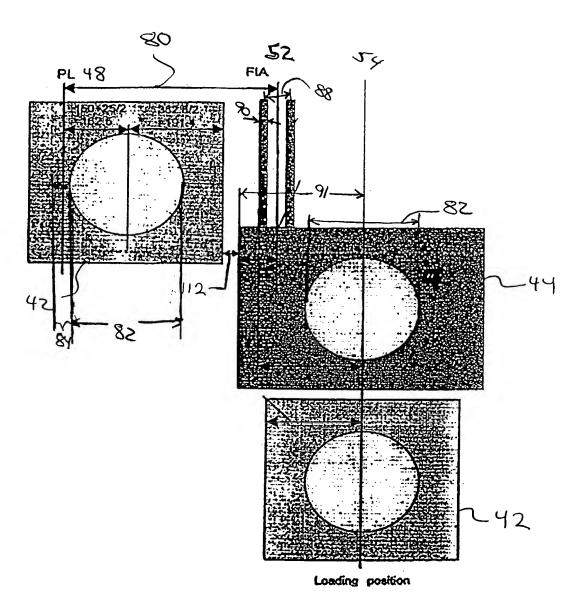


FIG. 11

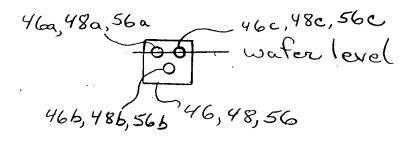


FIG. 12(A)



FIG. 12(B)



FIG. 12(C)



FIG. 12(D)

		p	
Wafer stage 42: Perform	m loading. Monitor X po	sition by 56a	
Changing to 56, Y position	on by 54 and Yaw by 54.		Section 1
a wafer Monitor Y nosi	ed to begin exposure section by 46, Y position by	quence if loaded with	200
See Fig. 14(a)	tion by 46, 1 position by	48, and Yaw by 48.	
33 T T(u)			
M-6	<del></del>		<del></del> ,
vvater stage 42: Start E	GA. Change to monitor	Y position by 52 and	
stage 44.	nent when necessary to	avoid disturbing	
Wafer stage 44: Contin	uo ovposina if looded		202
See Fig. 14(b)	de exposing in loaded.		
900 ( ig. 14(b)			
14/ (			
Water stage 42: Continu	ue EGA. Change to mor	nitor Y position by 50	
vvater stage 44: Stoppe	ed at the end of the expo	sure sequence.	204
See Fig. 14(c)		•	_ [
	Ţ		
Wafer stage 42: End FC	GA. Begin switching in th	ne V direction	
Change to monitor Yaw	by 52 and 50.	ie i direction.	206
Wafer stage 44: Switch	in the Y direction.		200
See Fig. 14(d)			
			_
Wafer stage 42: Switch	in the Y direction. Chan	ge to monitor X	
position by 56a.			000
Wafer stage 44: Wait to	switch in the Y direction.	Change to monitor	208
Y position by 56c when 5	i6c becomes available.		
See Fig. 14(e)			
Mofor stone 40. Weit in			7
Wafer stage 42: Wait in	the Y direction. Change	to monitor X	
position by 46 and Yaw b Wafer stage 44: Switch i	in the V direction	available.	210
See Fig. 14(f)	if the Fallection.	•	
			_].
Wafer stage 42: Switch i	n the Y direction.		7
Wafer stage 44: Switch i	n the Y direction. Chang	ge to monitor X	212
position by 56 and Yaw b	y 56.		1 - 1 -
See Fig. 14(g)			1
	To Fig. 12/b)		<del></del>
n Step 243	To Fig. 13(b)	FIG. 13(A)	
•	▼		

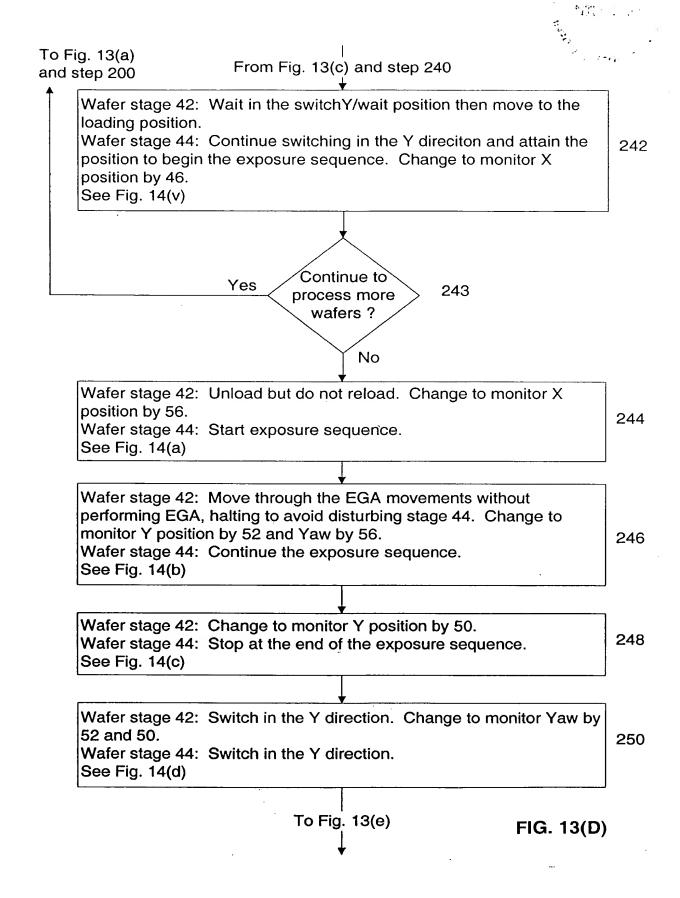
## To Fig. 13(a) and step 200

a step 200	
Wafer stage 42: Switch in the X direction. Change to monitor Y position by 48c. Wafer stage 44: Wait for stage 42 to finish moving. Change to monitor Y position by 48a. See Fig. 14(h)	214
	_
Wafer stage 42: Wait for stage 44 to finish moving. Wafer stage 44: Switch in the X direction. Change to monitor Y position by 52. See Fig. 14(i)	216
	_
Wafer stage 42: Start exposure sequence. Change to monitor Y position by 48.	
Wafer stage 44: Switch in the X direction. Change to monitor Y position by 54. See Fig. 14(j)	218
	ل
Wafer stage 42: Start exposure sequence. Wafer stage 44: Load the wafer. See Fig. 3	220
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<b>TAC</b> ( )	<b>-</b>
Wafer stage 42: Continue exposure sequence. Wafer stage 44: Continue loading. Change to monitor Y position by 52. See Fig. 14(I)	222
Wafer stage 42: Continue exposure sequence. Wafer stage 44: Perform EGA. See Fig. 14(m)	224
	J
Wafer stage 42: End exposure sequence. Wafer stage 44: Continue EGA. See Fig. 14(n)	226
	J
Wafer stage 42: Stop in the safety position and wait for stage 44 to finish EGA.	228
Wafer stage 44: End EGA. See Fig. 14(o)	
1	

To Fig. 13(c)

FIG. 13(B)

g. 13(a) step 200 From Fig. 13(b) and step 228	ال <b>ن</b> ارد
Wafer stage 42: Stop in the safety postiion. Wafer stage 44: Switch in the X direction. See Fig. 14(p)	230
	_
Wafer stage 42: Switch in the X direction. Change to monitor Y position by 50. Wafer stage 44: Wait for 48a to become available to control Y position. Resume switching in the X direction. See Fig. 14(q)	232
Wafer stage 42: Continue switching in the X direction. Wafer stage 44: Wait in the switch X/wait position. Change to monitor Y postiion by 48a. See Fig. 14(r)	234
	_
Wafer stage 42: Continue switching in the X direction. Change to monitor Y position by 52. Wafer stage 44: Wait in the switch X/wait position. Change to monitor Y position by 48 and Yaw by 48. See Fig. 14(s)	236
1	J
Wafer stage 42: Continue switching in the X direction. Change to monitor Y postion by 54 and Yaw by 54. Wafer stage 44: Wait in the switch X/wait position. See Fig. 14(t)	238
•	٠,
Wafer stage 42: Switch in the Y direction. Change to monitor X position by 56a. Wafer stage 44: Switch in the Y direction. Change to monitor X position by 56c. See Fig. 14(u)	240
	240



## From Fig. 13(d)

Wafer stage 42: Switch in the Y direction. Change to monitor X position by 56a. Wafer stage 44: Pause and wait for 56c to become available to 252 control X position. See Fig. 14(e) Wafer stage 42: Pause and wait for 46 to become available to control X position. 254 Wafer stage 44: Switch in the Y direction. See Fig. 14(f) Wafer stage 42: Switch in the Y direction. Wafer stage 44: Switch in the Y direction. Change to monitor X 256 position by 56 and Yaw by 56. See Fig. 14(g) Wafer stage 42: Switch in the X direction. Change to monitor Y position by 48c. 258 Wafer stage 44: Pause and wait for stage 42 to stop moving. Change to monitor Y position by 48b. See Fig. 14(h) Wafer stage 42: Pause switching in the X direction and wait for stage 44 to stop moving. 260 Wafer stage 44: Switch in the X direction. Change to monitor Y position by 52. See Fig. 14(i) Wafer stage 42: Change to monitor Y position by 48. Wafer stage 44: Remofe exposed wafer. Change to monitor Y 262 position by 54. See Fig. 14(j) End Process

FIG. 13(E)

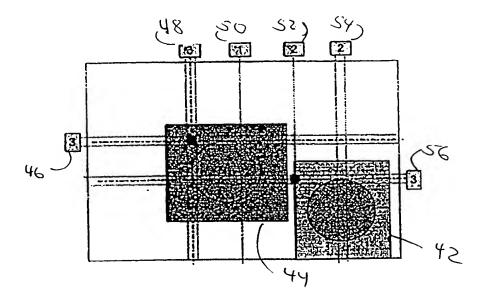


FIG. 14(A)

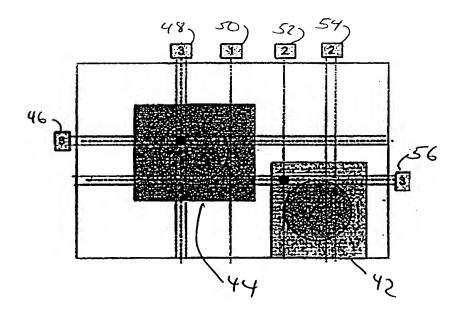


FIG. 14(B)

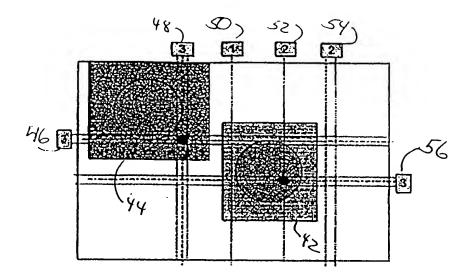


FIG. 14(C)

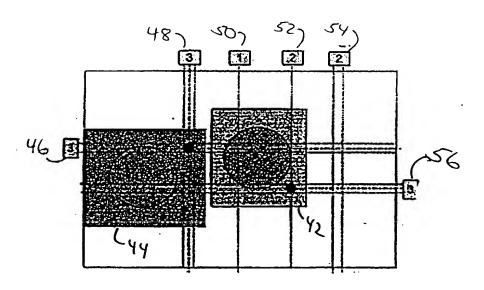


FIG. 14(D)

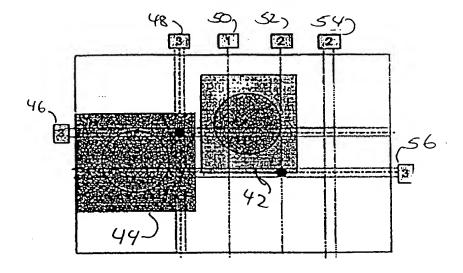


FIG. 14(E)

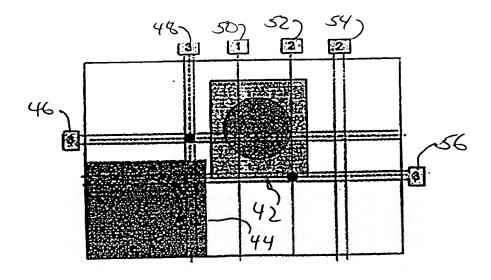


FIG. 14(F)

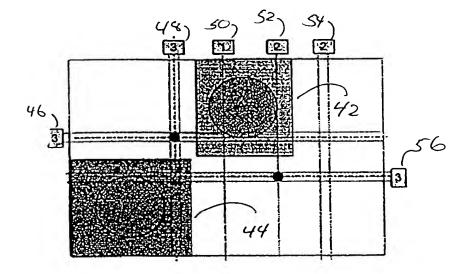


FIG. 14(G)

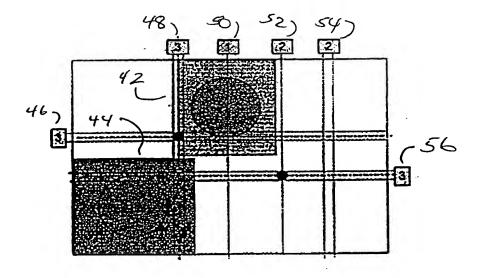


FIG. 14(H)

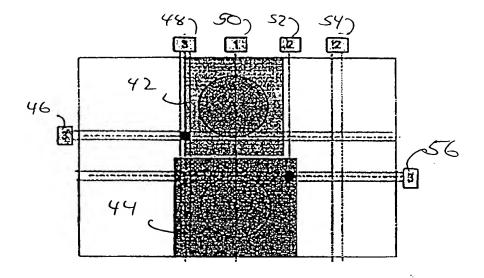


FIG. 14(I)

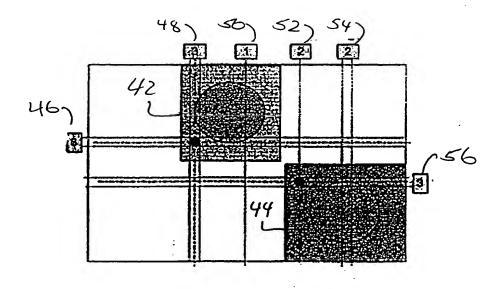
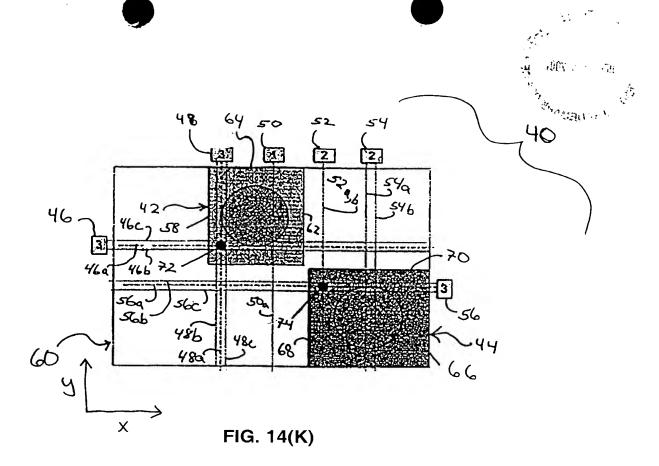


FIG. 14(J)



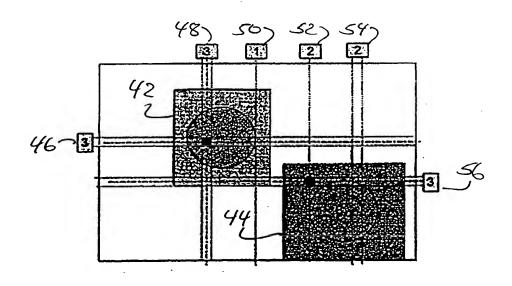


FIG. 14(L)

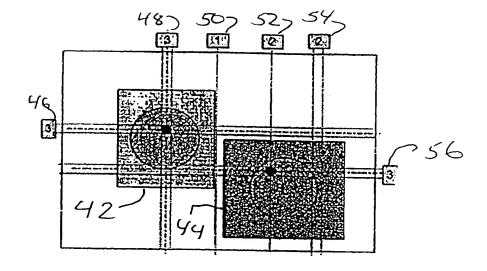


FIG. 14(M)

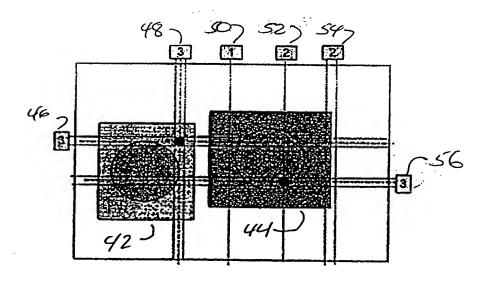


FIG. 14(N)

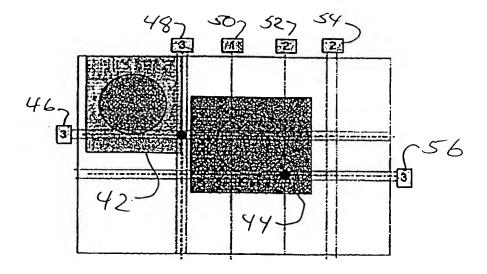


FIG. 14(0)

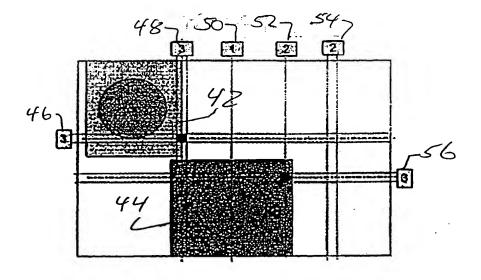


FIG. 14(P)

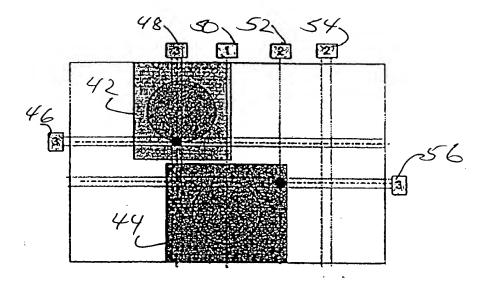


FIG. 14(Q)

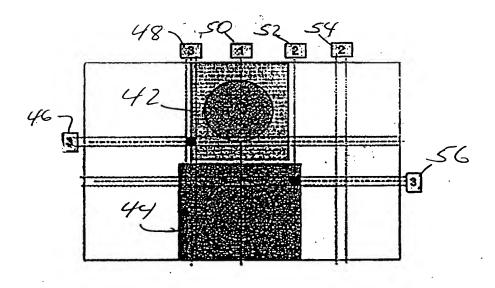


FIG. 14(R)

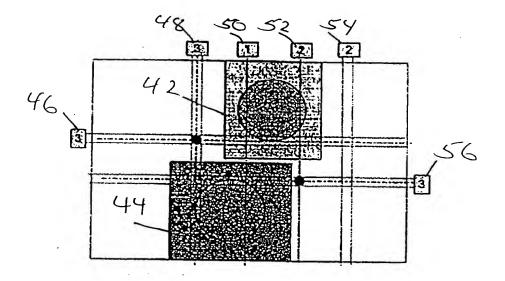


FIG. 14(S)

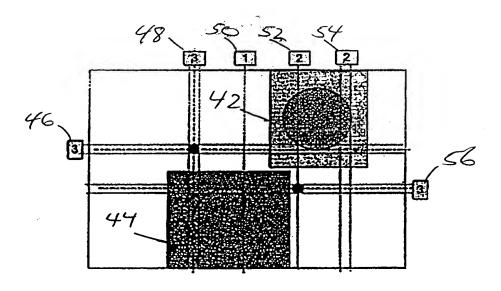


FIG. 14(T)

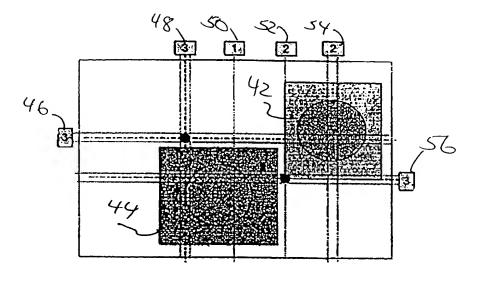


FIG. 14(U)

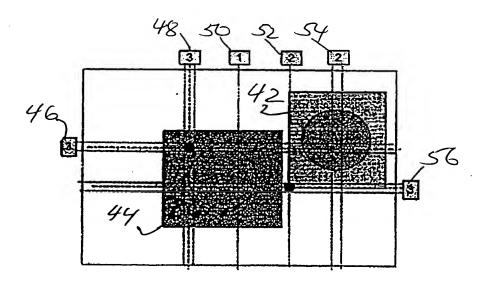


FIG. 14(V)